

**Listing of Claims:**

1. (Currently amended) A front-end array process for making a liquid crystal display panel, comprising:

depositing a molybdenum-containing metal layer on a glass substrate;

5 forming a patterned photoresist ~~and defining a gate and word line array pattern~~ on said molybdenum-containing metal layer, wherein said patterned photoresist defines a gate and word line array pattern; and

10 using said patterned photoresist as an etching ~~hard~~ mask, uniformly etching said molybdenum-containing metal layer to form said gate and word line array pattern having ~~slightly~~ substantially oblique sidewalls, wherein said etching of said molybdenum-containing metal layer uses gas mixture.

15 2. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein after said etching of said molybdenum-containing metal layer, an over etching is carried out.

20 3. (Currently amended) The front-end array process for making a liquid crystal display panel according to claim 1 wherein ~~oxygen/fluorine~~ fluorine/oxygen containing gas mixture is SF<sub>6</sub>/O<sub>2</sub> having a ratio of about 700sccm/300sccm.

4. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said etching of said molybdenum-containing metal layer is executed under a process pressure higher than 25 mTorr.

25 5. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said etching of said molybdenum-containing metal layer is further controlled by a source power, a bias power, process pressure, oxygen flowrate and flowrate of fluorine containing gas.

6. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said molybdenum-containing metal layer is a dual-metal layer.

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7. (Currently amended) The front-end array process for making a liquid crystal display panel according to claim 6 wherein said dual-metal layer is Mo/AlNd, MoW/AlNd, or MoW/Al, wherein Mo and MoW are top layers, while AlNd and Al are bottom layers.

10 8. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said etching of said molybdenum-containing metal layer is detected by an end-point detection method at an wavelength of about 704nm.

15 9. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is oxygen/fluorine containing.

10. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is oxygen/chlorine containing.

20 11. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is oxygen/chlorine/fluorine containing.

25 12. (Original) The front-end array process for making a liquid crystal display panel according to claim 1 wherein said gas mixture is SiF<sub>6</sub>/O<sub>2</sub> containing.

13. (Original) A front-end array process for making a liquid crystal display panel, comprising:

depositing a molybdenum-containing metal layer on a glass substrate;  
forming a patterned photoresist and defining a gate and word line array pattern on  
said molybdenum-containing metal layer; and  
etching said molybdenum-containing metal layer by said patterned photoresist to  
5 form said gate and word line array pattern.

14. (Currently amended) The front-end array process for making a liquid crystal display  
panel according to claim 13 wherein said gate and word line array pattern have  
slightly substantially oblique sidewalls.

15. (Original) The front-end array process for making a liquid crystal display panel  
according to claim 13 wherein after said etching of said molybdenum-containing  
metal layer, an over etching is carried out.

16. (Currently amended) The front-end array process for making a liquid crystal display  
panel according to claim 13 wherein ~~oxygen/fluorine~~ fluorine/oxygen containing gas  
mixture is SF<sub>6</sub>/O<sub>2</sub> having a ratio of about 700sccm/300sccm.

17. (Original) The front-end array process for making a liquid crystal display panel  
according to claim 13 wherein said etching of said molybdenum-containing metal  
layer is executed under a process pressure higher than 25 mTorr.

18. (Original) The front-end array process for making a liquid crystal display panel  
according to claim 13 wherein said etching of said molybdenum-containing metal  
layer is detected by an end-point detection method at a wavelength of about 704nm.

19. (Original) The front-end array process for making a liquid crystal display panel  
according to claim 13 wherein said molybdenum-containing metal layer is a

dual-metal layer.

20. (Currently amended) The front-end array process for making a liquid crystal display panel according to claim 19 wherein said dual-metal layer is Mo/AlNd, MoW/AlNd, or MoW/Al, wherein Mo and MoW are top layers, while AlNd and Al are bottom layers.